

| | L # | Hits | Search Text |
|----|-----|--------|-----------------------------------------------------------------|
| 11 | L11 | 2503 | (plurality near2 (mask or reticle)) with pattern\$3 |
| 12 | L12 | 102857 | (wafer or substrate) same (lithography or exposure or exposing) |
| 13 | L13 | 1522 | 11 and 12 |
| 14 | L14 | 1116 | (chang\$3 near3 (expos\$5 near2 amount)) |
| 15 | L15 | 48 | 13 and 14 |
| 16 | L16 | 18 | @ad<=19991108 and 15 |

PK
8/20/04

| | L # | Hits | Search Text |
|----|-----|-------|-----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|
| 1 | L1 | 10 | US-5461237-\$.DID. OR US-5486896-\$.DID. OR US-0553951-\$.DID. OR US-5593800-\$.DID. OR US-5710620-\$.DID. OR US-5801815-\$.DID. OR US-5841520-\$.DID. OR US-6213607-\$.DID. OR US-6337162-\$.DID. OR US-6463577-\$.DID. |
| 2 | L2 | 1 | ("5539521").PN. |
| 3 | L3 | 876 | ((wafer or substrate) near3 (sag\$4 or flex\$3 or deform\$5)) with (measur\$5 or detect\$4 or sens\$4 or determin\$5) |
| 4 | L4 | 53501 | (mask or reticle) same (lithography or exposure or exposing) |
| 5 | L5 | 172 | 3 and 4 |
| 6 | L6 | 430 | ((wafer or substrate) near3 (sag\$4 or flex\$3 or deform\$5)) with (correct\$4 or compensat\$4 or adjust\$5) |
| 7 | L7 | 52 | 5 and 6 |
| 8 | L8 | 31 | @ad<=19991108 and 7 |
| 9 | L9 | 1 | 628363.ap. and zero |
| 10 | L10 | 1 | 628363.ap. and chuck\$3 |